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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/892,023	06/26/2001	Kiyohiko Takagi	F-7041	1827
7:	590 07/15/2004		EXAMINER	
Jordan and Hamburg 122 East 42nd Street			COLEMAN, WILLIAM D	
New York, NY			ART UNIT	PAPER NUMBER
			2823	

DATE MAILED: 07/15/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	09/892,023	TAKAGI ET AL.			
Office Action Summary	Examiner	Art Unit			
·	W. David Coleman	2823	Bul		
The MAILING DATE of this communication app					
Period for Reply		,			
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply of If NO period for reply is specified above, the maximum statutory period with the set or extended period for reply will, by statute, any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tir within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communicatio D (35 U.S.C. § 133).	on.		
Status					
1) Responsive to communication(s) filed on 19 Ap	<u>oril 2004</u> .				
2a)⊠ This action is FINAL . 2b)□ This	This action is FINAL . 2b) ☐ This action is non-final.				
3) Since this application is in condition for allowar	☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is				
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 4	53 O.G. 213.			
Disposition of Claims					
4)⊠ Claim(s) <u>1-4,6-14 and 16-23</u> is/are pending in t	the application.				
4a) Of the above claim(s) is/are withdraw	·				
5) Claim(s) is/are allowed.					
6)⊠ Claim(s) <u>1-4, 6-14 and 16-23</u> is/are rejected.					
7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/o	r election requirement.				
Application Papers					
9)☐ The specification is objected to by the Examine	r.				
10)☐ The drawing(s) filed on is/are: a)☐ acce	epted or b) objected to by the	Examiner.			
Applicant may not request that any objection to the	drawing(s) be held in abeyance. Se	∋ 37 CFR 1.85(a).			
Replacement drawing sheet(s) including the correct		•	d).		
11)☐ The oath or declaration is objected to by the Ex	aminer. Note the attached Office	Action or form PTO-152.			
Priority under 35 U.S.C. § 119					
 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau 	s have been received. s have been received in Applicat rity documents have been receive	on No			
* See the attached detailed Office action for a list	of the certified copies not receive	ed.			
Attachment(s) 1) Notice of References Cited (PTO-892)	4) Interview Summary	(PTO-413)			
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail D	ate			
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	5) ☐ Notice of Informal F 6) ☐ Other:	Patent Application (PTO-152)			
S. Datast and To-day of Office	,				

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 2 and 3 are rejected under 35 U.S.C. 102(b) as being anticipated by Abraham et al., U.S. Patent 5,883,007.

2. Pertaining to claim 1, see **FIGS. 1-5** where <u>Abraham</u> teaches a dry etching process including:

providing a substrate 100 having a plurality of stacked layers including metal layers and a base of glass;

introducing a processing gas into a vacuum chamber to achieve a predetermined controlled pressure level therein;

applying radio frequency power 305/320 (see FIGS. 3) to a substrate 350 placed within the vacuum chamber 300 for generating plasma (not shown) in the vacuum chamber, whereby the substrate is processed, the substrate having a plurality of stacked layers including metal layers;

etching the layers on the substrate with the processing gas until a time point when the surface of a lowermost layer on the substrate is etched; and

adding CHF (column 13, line 42), gas to the processing gas for etching the lowermost layer on the substrate, wherein the processing gas is one of Cl₂ and a gaseous mixture containing Cl₂, and wherein CHF₃ is substantially absent from said processing gas prior to said step of adding CHF₃ (see Table 1, i.e., no CHF₃ in first chemistry and Table 2 i.e., includes CHF₃ in second chemistry).

- 3. Pertaining to claim 2, <u>Abraham</u> teaches the dry etching process according to Claim 1, wherein the etching process is effected through a method of determining a layer being processed (see figure 4).
- 4. Pertaining to claim 3, <u>Abraham</u> teaches the dry etching process according to Claim 1, wherein the lowermost layer on the substrate is the subject to be etched.
- 5. Pertaining to claim 4, <u>Abraham</u> teaches the dry etching process of claim 2, wherein the method of determining is monitoring the etching process by detecting plasma light intensity (column 6, lines 23-28).
- 6. Pertaining to claim 6, <u>Abraham</u> teaches the dry etching process of claim 4, wherein a non-aluminum reactive gas is added when the substrate includes a layer of aluminum.
- 7. Pertaining to claim 14, Abraham teaches the dry etching process of claim 2, wherein the method of determining is based upon the sampling data obtained from experimentation (see tables 1-4).
- 8. Pertaining to claim 16, Abraham teaches the dry etching process of claim 14, wherein a non-aluminum reactive gas is added when the substrate includes a layer of aluminum.

Claim Rejections - 35 USC § 103

- 9. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 10. Claims 7, 8, 9, 10, 11, 13, 17, 18, 19, 20, 21, 22 and 23 rejected under 35 U.S.C. 103(a) as being unpatentable over Abraham et al., U.S. Patent 5,883,007.
- 11. Abraham discloses a semiconductor process substantially as claimed.
- 12. Pertaining to claims 7, 8, 9, 10, 11, 17, 18, 19, 20 and 21 fails to teach any particular percentage of process gases as claimed. Given the teaching of the references, it would have been obvious to determine the optimum thickness, temperature as well as condition of delivery of the layers involved. See *In re Aller, Lacey and Hall* (10 USPQ 233-237) "It is not inventive to discover optimum or workable ranges by routine experimentation. Note that the specification contains no disclosure of either the critical nature of the claimed ranges or any unexpected results arising therefrom. Where patentability is said to be based upon particular chosen dimensions or upon another variable recited in a claim, the Applicant must show that the chosen dimensions are critical. *In re Woodruff*, 919 f.2d 1575, 1578, 16 USPQ2d 1934, 1936 (Fed. Cir. 1990).

Any differences in the claimed invention and the prior art may be expected to result in some differences in properties. The issue is whether the properties differ to such an extent that the difference is really unexpected. *In re Merck & Co.*, 800 F.2d 1091, 231 USPQ 375 (Fed. Cir. 1986)

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Appellants have the burden of explaining the data in any declaration they proffer as evidence of non-obviousness. *Ex parte Ishizaka*, 24 USPQ2d 1621, 1624 (Bd. Pat. App. & Inter. 1992).

An Affidavit or declaration under 37 CFR 1.132 must compare the claimed subject matter with the closest prior art to be effective to rebut a prima facie case of obviousness. *In re Burckel*, 592 F.2d 1175, 201 USPQ 67 (CCPA 1979).

- 13. Pertaining to claims 13 and 23, <u>Abraham</u> teaches the dry etching process according to one of Claims 7-21, wherein the metal layers of the plurality of stacked layers comprise an aluminum middle layer and titanium top and bottom layers.
- 14. Pertaining to claims 12 and 22, <u>Abraham</u> teaches the dry etching process according to one of claims 7-21, wherein the metal layers of the plurality of stacked layers comprise an aluminum middle layer and titanium top and bottom layers.

Conclusion

- 15. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).
- 16. A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event,

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however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

- 17. Any inquiry concerning this communication or earlier communications from the examiner should be directed to W. David Coleman whose telephone number is 571-272-1856. The examiner can normally be reached on 9:00 AM-5:00 PM.
- 18. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on 571-272-1855. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.
- 19. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

W. David Coleman Primary Examiner Art Unit 2823

WDC